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Anodizing treatments for titanium implants

J. A. Disegi
Proceedings of the 1997 16 Southern Biomedical Engineering Conference
Year: 1997
Anodizing treatments for titanium implants
J. A. Disegi
Proceedings of the 1997 16 Southern Biomedical Engineering Conference
Year: 1997
Pages: 129 - 132
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IEEE Conferences
Abstract (352 Kb)

Influence of pH on the Reactive Brilliant Red X-3B Wastewater Treatment by an Al-Cu Bimetallic System

Jin-Hong Fan | Hong-Wu Wang | De-Li Wu | Lu-Ming MA
2008 2nd International Conference on Bioinformatics and Biomedical Engineering
Year: 2008
Influence of pH on the Reactive Brilliant Red X-3B Wastewater Treatment by an Al-Cu Bimetallic System
Jin-Hong Fan; Hong-Wu Wang; De-Li Wu; Lu-Ming MA
2008 2nd International Conference on Bioinformatics and Biomedical Engineering
Year: 2008
Pages: 3264 - 3268
IEEE Conferences
Abstract (344 Kb)

Inverted pyramid texturisation without photolithography for multicrystalline solar cell

Der-Chin Wu | D. Z. Dimitrov | Ching-Hsi Lin | Chen-Hsun Du | Wei-Chih Hsu | Wen-Haw Lu | Chung-Wen Lan
2010 35th IEEE Photovoltaic Specialists Conference
Year: 2010
Inverted pyramid texturisation without photolithography for multicrystalline solar cell
Der-Chin Wu; D. Z. Dimitrov; Ching-Hsi Lin; Chen-Hsun Du; Wei-Chih Hsu; Wen-Haw Lu; Chung-Wen Lan
2010 35th IEEE Photovoltaic Specialists Conference
Year: 2010
Pages: 003233 - 003236
IEEE Conferences

Abstract

(1352 Kb)

Enhancement or reduction of catalytic dissolution reaction in chemically amplified resists by substrate contaminants

Choi Pheng Soo | S. Valiyaveetil | A. Huan | A. Wee | Ting Cheong Ang | M. H. Fan | A. J. Bourdillon | Lap Hung Chan

IEEE Transactions on Semiconductor Manufacturing

Year: 1999 | Volume: 12 | Issue: 4

☐ **Enhancement or reduction of catalytic dissolution reaction in chemically amplified resists by substrate contaminants**

Choi Pheng Soo; S. Valiyaveetil; A. Huan; A. Wee; Ting Cheong Ang; M. H.

Fan; A. J. Bourdillon; Lap Hung Chan

IEEE Transactions on Semiconductor Manufacturing

Year: 1999, Volume: 12, Issue: 4

Pages: 462 - 469

Cited by: Papers (7) | Patents (10)

IEEE Journals & Magazines

Abstract

(524 Kb)

Particle removal from silicon wafer **surface** in wet cleaning process

M. Itano | F. W. Kern | M. Miyashita | T. Ohmi

IEEE Transactions on Semiconductor Manufacturing

Year: 1993 | Volume: 6 | Issue: 3

☐ **Particle removal from silicon wafer **surface** in wet cleaning process**

M. Itano; F. W. Kern; M. Miyashita; T. Ohmi

IEEE Transactions on Semiconductor Manufacturing

Year: 1993, Volume: 6, Issue: 3

Pages: 258 - 267

Cited by: Papers (40) | Patents (5)

IEEE Journals & Magazines

Abstract

(780 Kb)

Study of chemical staining on metallization for SEM image quality effect improvement

Chan Sieng Fong | Ng Hong Seng

2008 IEEE International Conference on Semiconductor Electronics

Year: 2008

☐ **Study of chemical staining on metallization for SEM image quality effect improvement**

Chan Sieng Fong; Ng Hong Seng

2008 IEEE International Conference on Semiconductor Electronics

Year: 2008

Pages: 410 - 413

IEEE Conferences

Abstract

(1293 Kb)

Variable structure control of pH neutralization of a prototype waste water **treatment** plant using LabVIEW

S. Harivardhini | A. Raghuram

2015 IEEE Conference on Systems, Process and Control (ICSPC)

Year: 2015

☐ **Variable structure control of pH neutralization of a prototype waste water **treatment** plant using LabVIEW**

S. Harivardhini; A. Raghuram

2015 IEEE Conference on Systems, Process and Control (ICSPC)

Year: 2015
Pages: 79 - 84
IEEE Conferences

Abstract (2869 Kb)

Novel electrolysis-ionized-water cleaning technique for the chemical-mechanical polishing (CMP) process

H. Aoki | T. Nakajima | K. Kikuta | Y. Hayashi
Proceedings of 1994 VLSI Technology Symposium
Year: 1994

☐ **Novel electrolysis-ionized-water cleaning technique for the chemical-mechanical polishing (CMP) process**
H. Aoki; T. Nakajima; K. Kikuta; Y. Hayashi
Proceedings of 1994 VLSI Technology Symposium
Year: 1994
Pages: 79 - 80
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Abstract (188 Kb)

Surface properties of the substratum affect human mesenchymal stem cell differentiation

M. S. Godbole | A. Seyda | J. Kohn | T. Livingston Arinzeh
IEEE 30th Annual Northeast Bioengineering Conference, 2004. Proceedings of the
Year: 2004

☐ **Surface properties of the substratum affect human mesenchymal stem cell differentiation**
M. S. Godbole; A. Seyda; J. Kohn; T. Livingston Arinzeh
IEEE 30th Annual Northeast Bioengineering Conference, 2004. Proceedings of the
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